

**A THIN-FILM FORMING APPARATUS HAVING AN AUTOMATIC
CLEANING FUNCTION FOR CLEANING THE INSIDE**

Abstract of the Disclosure

5 A thin-film forming apparatus includes: (a) a reaction chamber for forming a thin film on a workpiece placed on a susceptor provided in the reaction chamber; and (b) a cleaning device for cleaning unwanted deposits adhering to the inside of the reaction chamber at predetermined intervals. The cleaning device includes: (i) a cleaning gas controller for introducing a cleaning gas into the reaction chamber and evacuating the reaction chamber after the cleaning treatment; (ii) a cleaning gas activator for activating the cleaning gas in radical form; and (iii) a temperature and timing controller programmed to reduce the temperature of the susceptor at a predetermined rate for cleaning after completion of film formation and then to actuate the cleaning gas controller and the cleaning gas activator.

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